

ABSTRACT

A blank mask includes a transparent substrate and a multilayer light shielding film disposed on the transparent substrate, the multilayer light shielding film including a transition metal and at least any one between oxygen and nitrogen, the multilayer light shielding film including a first light shielding film and a second light shielding film disposed on the first light shielding film, and the multilayer light shielding film having an EA (Edge side Area damaged) value of 2 nm^2 or less.

FIG. 1